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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/050,195	01/16/2002	Sang-Bom Kang	5649-912	6301
	7590 03/26/200 L SIBLEY & SAJOVE	EXAMINER		
PO BOX 37428			IM, JUNGHWA M	
RALEIGH, NC 27627		·	ART UNIT	PAPER NUMBER
			2811	
SHORTENED STATUTOR	Y PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE	
3 MONTHS		03/26/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

		GH.
	Application No.	Applicant(s)
	10/050,195	KANG ET AL.
Office Action Summary	Examiner	Art Unit
	Junghwa M. Im	2811
The MAILING DATE of this communic Period for Reply	ation appears on the cover sheet with	h the correspondence address
A SHORTENED STATUTORY PERIOD FO WHICHEVER IS LONGER, FROM THE MA - Extensions of time may be available under the provisions of after SIX (6) MONTHS from the mailing date of this communing of the provision of t	ILING DATE OF THIS COMMUNIC 137 CFR 1.136(a). In no event, however, may a repnication. utory period will apply and will expire SIX (6) MONT. ill, by statute, cause the application to become ABA	ATION. ply be timely filed THS from the mailing date of this communication. ANDONED (35 U.S.C. § 133).
Status		
1)⊠ Responsive to communication(s) filed	on 01 December 2006.	
· · · · · · · · · · · · · · · · · · ·	o)⊠ This action is non-final.	
3) Since this application is in condition for closed in accordance with the practice	· ·	
Disposition of Claims		
4) ☑ Claim(s) <u>1,3-7,13,14 and 25-31</u> is/are 4a) Of the above claim(s) is/are 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) <u>1,3-7,13,14 and 25-31</u> is/are 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction	e withdrawn from consideration.	
Application Papers		
9) The specification is objected to by the		
10)⊠ The drawing(s) filed on <u>16 January 20</u>		
Applicant may not request that any object		
Replacement drawing sheet(s) including to the state of th		
Priority under 35 U.S.C. § 119		·
12) Acknowledgment is made of a claim for a) All b) Some * c) None of: 1. Certified copies of the priority do a. Certified copies of the priority do a. Copies of the certified copies of application from the Internation	ocuments have been received. ocuments have been received in Ap f the priority documents have been r	oplication No
* See the attached detailed Office action	•	eceived.
Attachment(s)		
1) Notice of References Cited (PTO-892)		ummary (PTO-413)
 Notice of Draftsperson's Patent Drawing Review (PTo3) Information Disclosure Statement(s) (PTO-1449 or Paper No(s)/Mail Date 5/2006. 		/Mail Date formal Patent Application (PTO-152)

DETAILED ACTION

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 1 and 25 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claim 1 recites the limitation of "a capacitor disposed on an upper surface of the TiN contact plug opposite the substrate and comprising a lower electrode that contacts an upper surface of the TiN contact plug and an upper surface of the TiN liner layer." It is confusing since the capacitor is formed on the substrate, not opposite the substrate.

Claim 25 recites the limitation of "the capacitor is disposed on an upper surface of the TiN plug opposite the lower conductive layer." It is confusing since the lower conductive layer is a part of the capacitor.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 1, 3-7, 13, 25-29 and 30 are rejected under 35 U.S.C. 103(a) as being unpatentable over Chang et al. (US 5,672,542), hereinafter Chang in view of Taguwa et al. (US 6,107,190), hereinafter Taguwa and Moise et al. (US 6,534,809), hereinafter Moise.

Regarding claims 1 and 25, insofar as understood Fig.1 of Chang shows a contact plug in an insulating layer 20 having tensile stress (col. 1, lines 53-54), a TiN layer 26 surrounding the plug on contact and having compressive stress (col. 1, lines 32-33) and an ohmic layer 24 between the insulating layer and the TiN layer.

Chang discloses substantially the entire claimed device except a TiN plug. Taguwa teaches a TiN plug having a tensile stress (col. 2, lines 33-39) in lieu of W plug of Chang. It would have been obvious to one of ordinary skill in the art at the time of the invention to form a TiN plug in the device of Chang with Taguwa's teaching in order to reduced a production cost as taught in column 1, lines 57-61 of Taguwa.

The device with the teachings of Chang and Taguwa fails to show that a lower electrode of the capacitor structure contacting the upper surface of the TiN plug. Fig.1 of Moise shows a bottom electrode 124 of a capacitor 125 formed on a TiN contact plug 114 (col. 7, lines 43-50). It would have been obvious to one of ordinary skill in the art at the time of the invention to incorporate Moise's teaching to the device of Chang and Taguwa in order to fabricate a DRAM array with a charge storage capacitor.

Regarding claim 3, the liner of Chang inherently possesses an amorphous structure since it is deposited by CVD.

Regarding claims 4-5, Fig. 1 of Chang shows an ohmic layer, Ti 24 between the liner and the insulating layer.

Regarding claim 6, the combination of Chang/Taguwa/Mori does not explicitly disclose the thickness of the ohmic layer asclaimed. However, it would have been obvious to one of ordinary skill in the art at the time of the invention to have the recited range of the thickness for an ohmic layer to improve the conductivity, since it would have been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only in routine skill in the art. *In re Aller*, 105 USPQ 233.

Regarding claim 7, the combination of Chang/Taguwa/Mori does not explicitly show the thickness of the linerlayer as claimed. However, it would have been obvious to one of ordinary skill in the art at the time of the invention to have the recited range of the thickness for an liner layer to enhance the adherence, since it would have been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only in routine skill in the art. *In re Aller*, 105 USPQ 233.

Regarding claim 13, Fig.1 of Moise shows a capacitor 125 formed on a contact plug 114 and a capacitor with a lower electrode 124 made of Pt (col. 9, lines 27-39).

Regarding claim 26, Taguwa discloses a TiN plug formed by CVD (col.1, lines 57-61).

Regarding claim 27, Chang discloses a TiN layer formed by CVD (col. 3, lines 13-14). In addition, CVD, ALD, CVD AND ALD are a process designation and would thus not carry patentable weight in this claim drawn to a product. See *In re Thorp*, 227 USPQ 964 (Fed. Cir. 1985).

Regarding claim 28, Chang discloses a TiN layer has an amorphous crystal structure since it is deposited by PVC.

Regarding claim 29. Chang discloses a TiN liner formed by physical vapor deposition

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(col. 3, line 13). In addition, IPVD is a process designation and would thus not carry patentable weight in this claim drawn to a product. See *In re Thorp*, 227 USPO 964 (Fed. Cir. 1985).

Regarding claim 31, Moise shows the upper conductive layer made of Pt (col.9, lines 30-33).

Regarding claim 32, Moise shows the upper conductive layer (51) comprising a lower electrode of a capacitor (col. 9, lines 27-29).

Claims 14 and 30 are rejected under 35 U.S.C. 103(a) as being unpatentable over Chang in view of Mori and Taguwa applied to claims 1 and 25 further in view of Nagasaka et al. (US 6,300,683), hereinafter Nagasaka.

Regarding claims 14 and 30, the combination of Chang/Mori/Taguwa discloses most aspects of the instant invention except a shape of the contact plug. However, Fig. 19D of Nagasaka shows a tapered contact plug 12.

It would have been obvious to one of ordinary skill in the art at the time of the invention to form a tapered contact plug of Chang/Mori/taguwa with Nagasaka's teaching in order to form the plug without cracks. It is well known in the art that it is easier to fill contact/plug openings with tapered sidewalls.

Response to Arguments

Applicant's arguments with respect to pending claims have been considered but are moot in view of the new ground(s) of rejection.

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Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Junghwa M. Im whose telephone number is (571) 272-1655. The examiner can normally be reached on MON.-FRI. 8:30AM-5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Richard T. Elms can be reached on (571) 272-1869. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Junghwa M. Im

Examiner

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jmi